	L #	Hits	Search Text	DBs
1	L1	3995	(light adj guide).ti,ab.	US-PGPUB; USPAT
2	L2	131097	(mold$4 or stamp$4).ti,ab.	US-PGPUB; USPAT
3	L3	161	1 and 2	US-PGPUB; USPAT
4	L5	72551	(resist or photoresist or photopolymer$8 or photosensitiv$8 or photocross$8 or (light or radiat$8 or irradiat$8 or uv or ultraviolet or photo) near3 (sensitiv$8 or polymer or polymeriz$8 or polymeris$8 or crosslink$8 or cross adj link$8)).ti,ab.	US-PGPUB; USPAT
5	L6	23	3 and 5	US-PGPUB; USPAT
6	L7	2382331	(substrate or support)	US-PGPUB; USPAT
7	L8	170961	treat$8 near3 surface	US-PGPUB; USPAT
8	L9	27569	7 with 8	US-PGPUB; USPAT
9	L10	2	3 and 9	US-PGPUB; USPAT
10	L11	2250431	(deposit$8 or metal$6)	US-PGPUB; USPAT
11	L12	488373	7 with 11	US-PGPUB; USPAT
12	L13	40	3 and 12	US-PGPUB; USPAT
13	L14	516232	(rough$8 or blast$8 or sandblast$8)	US-PGPUB; USPAT

	L #	Hits	Search Text	DBs
14	L15	40882	7 with 14	US-PGPUB; USPAT
15	L16	2	3 and 15	US-PGPUB; USPAT
16	L17	358236	etch$4	US-PGPUB; USPAT
17	L18	3090779	surface	US-PGPUB; USPAT
18	L19	59413	7 with 17 with 18	US-PGPUB; USPAT
19	L21	13	3 and 19	US-PGPUB; USPAT
20	L22	529273	surface near3 activat$8 or plasma or surfactant	US-PGPUB; USPAT
21	L23	74401	7 with 22	US-PGPUB; USPAT
22	L24	5	3 and 23	US-PGPUB; USPAT
23	L25	69030	(resist or photoresist or photopolymer$8 or photosensitiv$8 or photocross$8 or (light or radiat$8 or irradiat$8 or uv or ultraviolet or photo) near3 (sensitiv$8 or polymer or polymeriz$8 or polymeris$8 or crosslink$8 or cross adj link$8)) with (adhes$8 or adher$8 or bond$8 or attach$8)	US-PGPUB; USPAT
24	L26	17563	7 with 25	US-PGPUB; USPAT
25	L27	6	3 and 26	US-PGPUB; USPAT
26	L28	4067	(microlens$4 or micro adj lens$4 or lens$4 near3 array or lenslet).ti,ab.	US-PGPUB; USPAT

	L #	Hits	Search Text	DBs
27	L29	143	2 and 28	US-PGPUB; USPAT
28	L30	62	29 and (9 or 12 or 15 or 19 or 23 or 26)	US-PGPUB; USPAT
29	L31	4394	430/320,321,330.ccls.	US-PGPUB; USPAT
30	L32	17	(3 or 29) and 31	US-PGPUB; USPAT
31	L33	844	264/1.24,2.5.ccls.	US-PGPUB; USPAT
32	L34	67	(1 or 28) and 33	US-PGPUB; USPAT
33	L35	21962	(light adj guide)	US-PGPUB; USPAT
34	L36	30089	(microlens$4 or micro adj lens$4 or lens$4 near3 array or lenslet)	US-PGPUB; USPAT
35	L37	807023	(mold$4 or stamp$4)	US-PGPUB; USPAT
36	L39	2816	(35 or 36) with 37	US-PGPUB; USPAT
37	L40	232	39 same (9 or 12 or 15 or 19 or 23 or 26)	US-PGPUB; USPAT
38	L41	575269	(resist or photoresist or photopolymer$8 or photosensitiv$8 or photocross$8 or (light or radiat$8 or irradiat$8 or uv or ultraviolet or photo) near3 (sensitiv$8 or polymer or polymeriz$8 or polymeris$8 or crosslink$8 or cross adj link$8))	US-PGPUB; USPAT
39	L42	74	40 same 41	US-PGPUB; USPAT

	L #	Hits	Search Text	DBs
40	L43	37	42 not (6 or 10 or 13 or 16 or 21 or 24 or 27 or 30 or 32 or 34)	US-PGPUB; USPAT
41	L44	11	chen-irene$.in.	US-PGPUB; USPAT
42	L45	6	lay-jyh$.in.	US-PGPUB; USPAT
43	L46	31	chou-tien$.in.	US-PGPUB; USPAT
44	L47	48	wang-yuan$.in.	US-PGPUB; USPAT
45	L48	372	yang-chin$.in.	US-PGPUB; USPAT
46	L49	41	hsu-chuan$.in.	US-PGPUB; USPAT
47	L50	16	(1 or 2 or 28) and (44 or 45 or 46 or 47 or 48 or 49)	US-PGPUB; USPAT
48	L51	18324	(microlens$4 or micro adj lens$4 or lens$4 near3 array or lenslet)	EPO; JPO; DERWENT; IBM_TDB
49	L52	33482	light adj guide	EPO; JPO; DERWENT; IBM_TDB
50	L53	624852	mold$4 or stamp$4	EPO; JPO; DERWENT; IBM_TDB

	L #	Hits	Search Text	DBs
51	L54	2364	(51 or 52) and 53	EPO; JPO; DERWENT; IBM_TDB
52	L55	474765	(resist or photoresist or photopolymer$8 or photosensitiv$8 or photocross$8 or (light or radiat$8 or irradiat$8 or uv or ultraviolet or photo) near3 (sensitiv$8 or polymer or polymeriz$8 or polymeris$8 or crosslink$8 or cross adj link$8))	EPO; JPO; DERWENT; IBM_TDB
53	L56	224	54 and 55	EPO; JPO; DERWENT; IBM_TDB
54	L57	2865924	substrate or support	EPO; JPO; DERWENT; IBM_TDB
55	L58	123456	treat$8 near3 surface	EPO; JPO; DERWENT; IBM_TDB
56	L59	12855	57 with 58	EPO; JPO; DERWENT; IBM_TDB
57	L60	2	56 and 59	EPO; JPO; DERWENT; IBM_TDB

	L #	Hits	Search Text	DBs
58	L61	319499	(deposit$8 or metal$4) with 57	EPO; JPO; DERWENT; IBM_TDB
59	L62	39	56 and 61	EPO; JPO; DERWENT; IBM_TDB
60	L63	259858	(rough$8 or blast$8 or sandblast$8)	EPO; JPO; DERWENT; IBM_TDB
61	L64	19181	57 with 63	EPO; JPO; DERWENT; IBM_TDB
62	L65	1	56 and 64	EPO; JPO; DERWENT; IBM_TDB
63	L66	14146	(etch$4 near5 surface) with 57	EPO; JPO; DERWENT; IBM_TDB
64	L67	5	56 and 66	EPO; JPO; DERWENT; IBM_TDB

	L #	Hits	Search Text	DBs
65	L68	8	54 and 64	EPO; JPO; DERWENT; IBM_TDB
66	L69	43420	(resist or photoresist or photopolymer$8 or photosensitiv$8 or photocross$8 or (light or radiat$8 or irradiat$8 or uv or ultraviolet or photo) near3 (sensitiv$8 or polymer or polymeriz$8 or polymeris$8 or crosslink$8 or cross adj link$8)) with (adhes$8 or adher$8 or bond$8 or attach$8)	EPO; JPO; DERWENT; IBM_TDB
67	L70	17	54 and 69	EPO; JPO; DERWENT; IBM_TDB
68	L71	365361	surface near3 activat$8 or plasma or surfactant	EPO; JPO; DERWENT; IBM_TDB
69	L72	48766	57 with 71	EPO; JPO; DERWENT; IBM_TDB
70	L73	6	56 and 72	EPO; JPO; DERWENT; IBM_TDB